AMENDMENT & RESPONSE UNDER 37 C.F.R. § 1.116 - EXPEDITED PROCEDURE

Serial Number: 09/817.447

Filing Date: March 26, 2001

Title: METHODS FOR MAKING COPPER AND OTHER METAL INTERCONNECTIONS IN INTEGRATED CIRCUITS

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a copper conductor within the trench or hole and on the first diffusion barrier, with the second diffusion barrier having lesser wettability with copper than the [zinc oxide material] first diffusion barrier.

(Amended)

An integrated-circuit assembly comprising:

an insulative layer having opposing first and second major surface, with the first major surface having a trench or hole, the trench or hole having an edge;

- a first diffusion barrier having an in-portion lining the trench or hole and having

  an out-portion outside the trench or hole and on the first major surface,

  with the out-portion having an edge adjacent the edge of the trench or

  hole, the first diffusion barrier consisting essentially of tungsten, titaniumtungsten, or titanium nitride;
- a second diffusion barrier on the <u>out-portion of the first diffusion barrier</u>

  [insulative layer] and having an edge substantially flush with a least a portion of the edge of the [trench or hole] <u>first diffusion barrier</u>;
- a copper conductor within the trench or hole and on the first diffusion barrier, with the second diffusion barrier having lesser wettabillity with copper than the [zinc oxide material] first diffusion barrier.

## **REMARKS**

Claims 38-76 are pending in the application. Of these, claims 38-45 stand allowed, claims 60, 61, 74, and 75 stand allowable if rewritten in appropriate independent form, claims 46-55 stand rejected under 35 USC §112, and claims 56-59 and 62-73 and 76 stand rejected under 35 USC §102.

## **Information Disclosure Statements**

Applicant respectfully requests that initialed copies of the 1449 Forms submitted with the Information Disclosure Statements filed on March 26, 2001 and May 16, 2001, acknowledging consideration of the identified references, be returned with the next official communication.